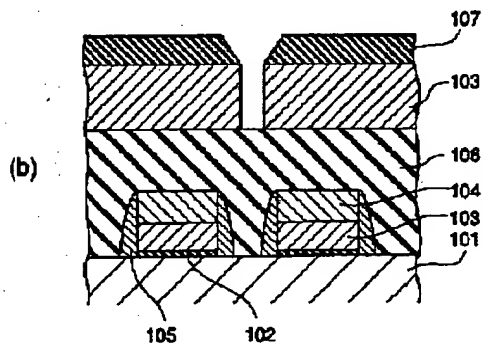


Patent Abstracts of Japan

TITLE : FORMATION OF FINE CONNECTION
HOLE



SOLUTION: A mask layer 103 is formed on a substrate 101, having a film for forming the fine connection hole. A antireflection film 107 is formed on the mask layer 103. A hole, having a diameter decreasing toward the substrate 101 side, is formed in the antireflection film 107. A pattern for forming a fine connection hole is formed in the mask layer 103, using the reflection preventing film 107 having a hole. The fine connection hole is formed in the film, in accordance with the pattern for forming the fine connection hole.

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